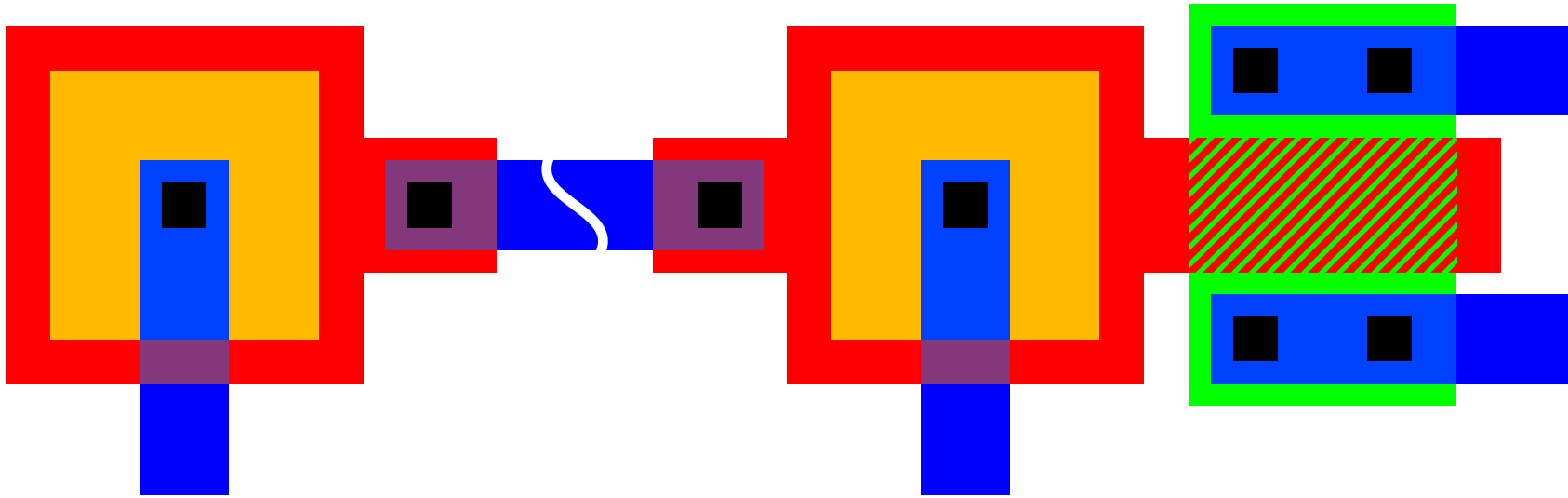
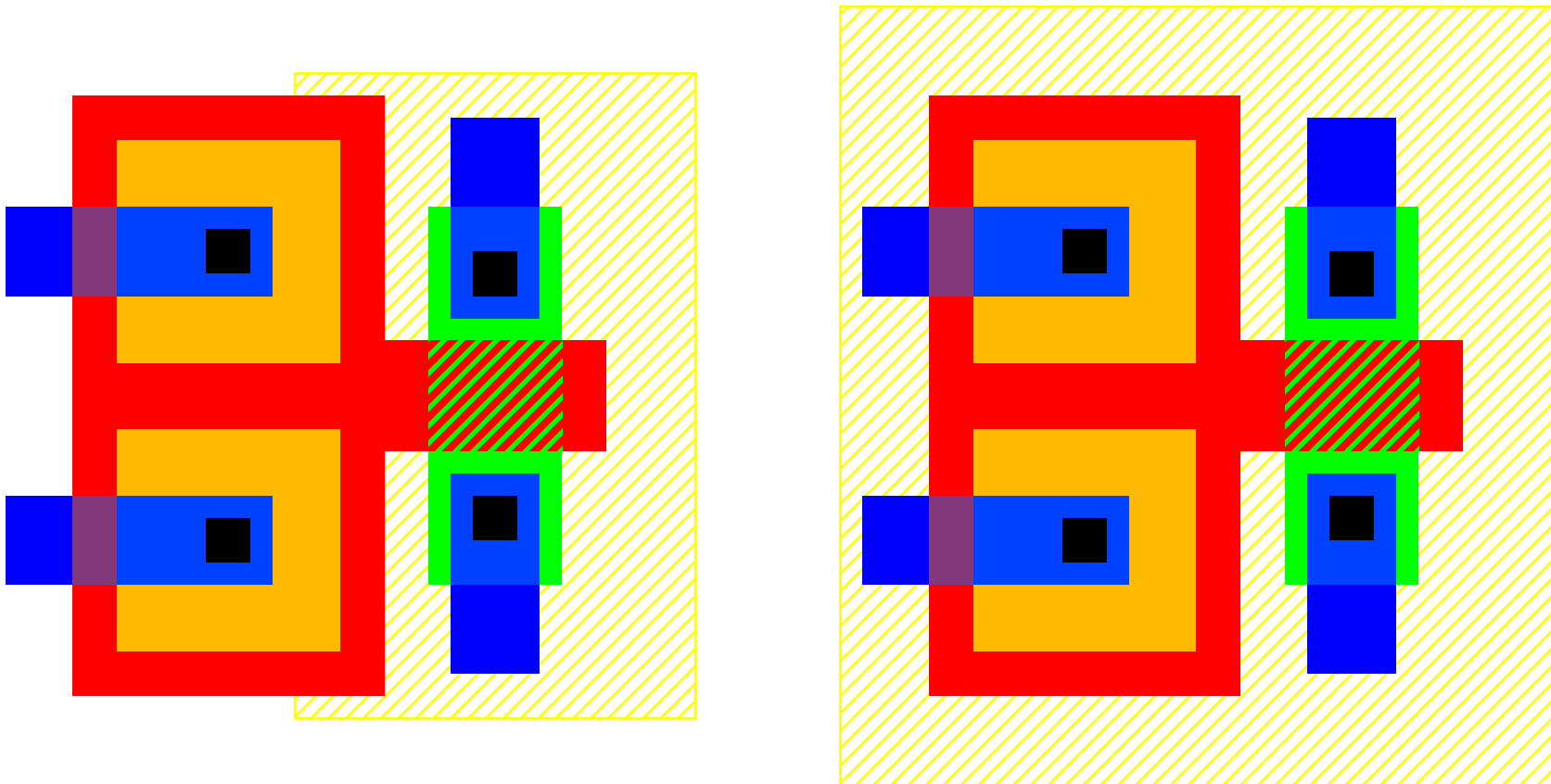


# How to Make Leaky Floating Gates...



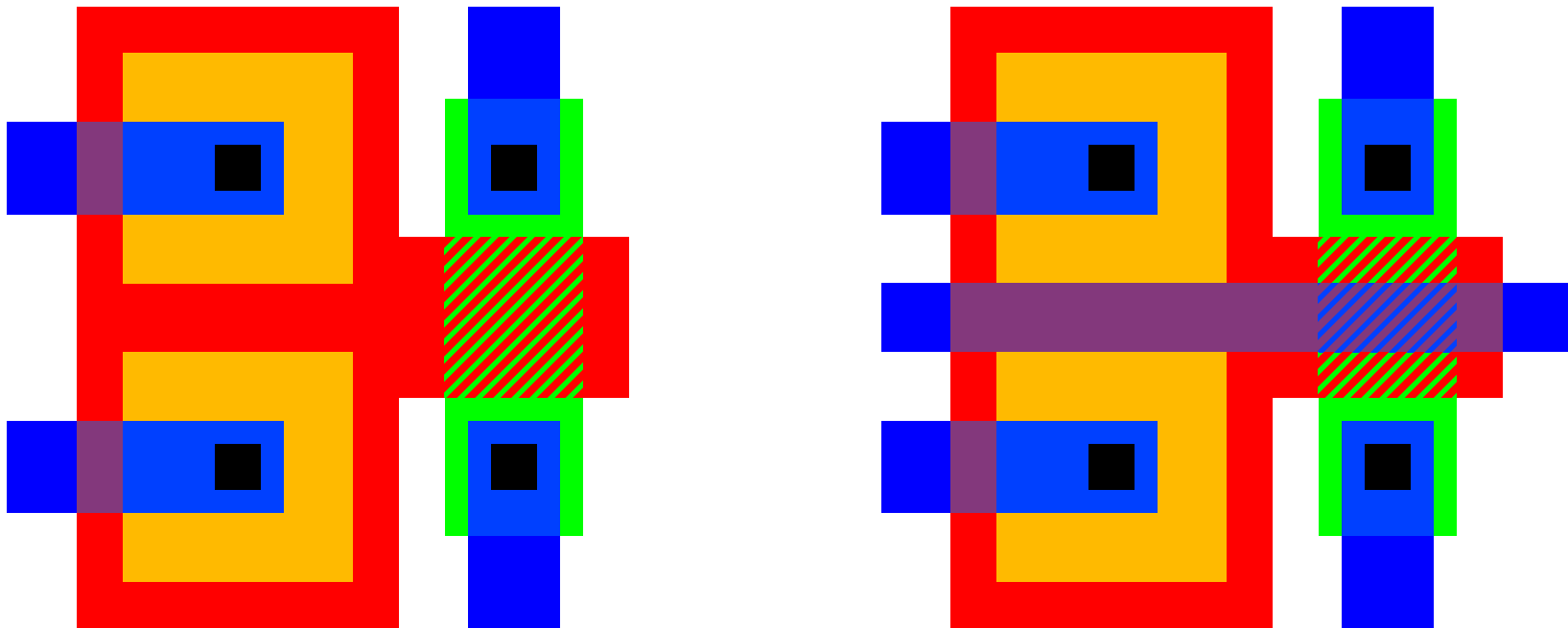
- ▶ Keep your floating gates on poly1.
- ▶ If you make a contact to metal, your gate will probably leak, because the oxide surrounding the metal layers are typically deposited rather than thermally grown.

# Beware of Capacitive Coupling from Below...



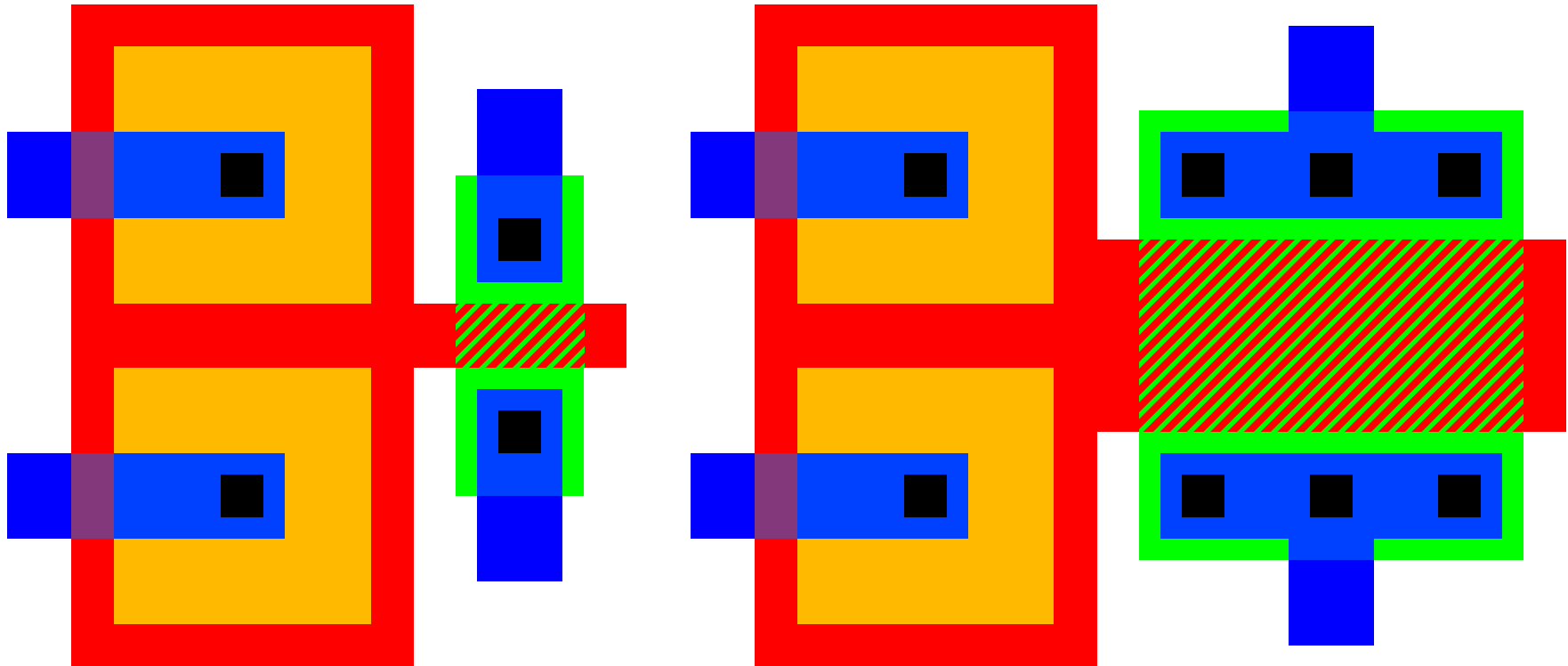
- ▶ If possible, don't allow a floating gate to cross a well boundary. For a *p*FGMOS, keep it entirely over the well. For an *n*FGMOS, keep it entirely over the substrate.
- ▶ If you split the area evenly between the substrate and the well, your floating-gate voltage will have a dependence on  $V_{DD}$  that you didn't expect...

# Beware of Capacitive Coupling from Above...

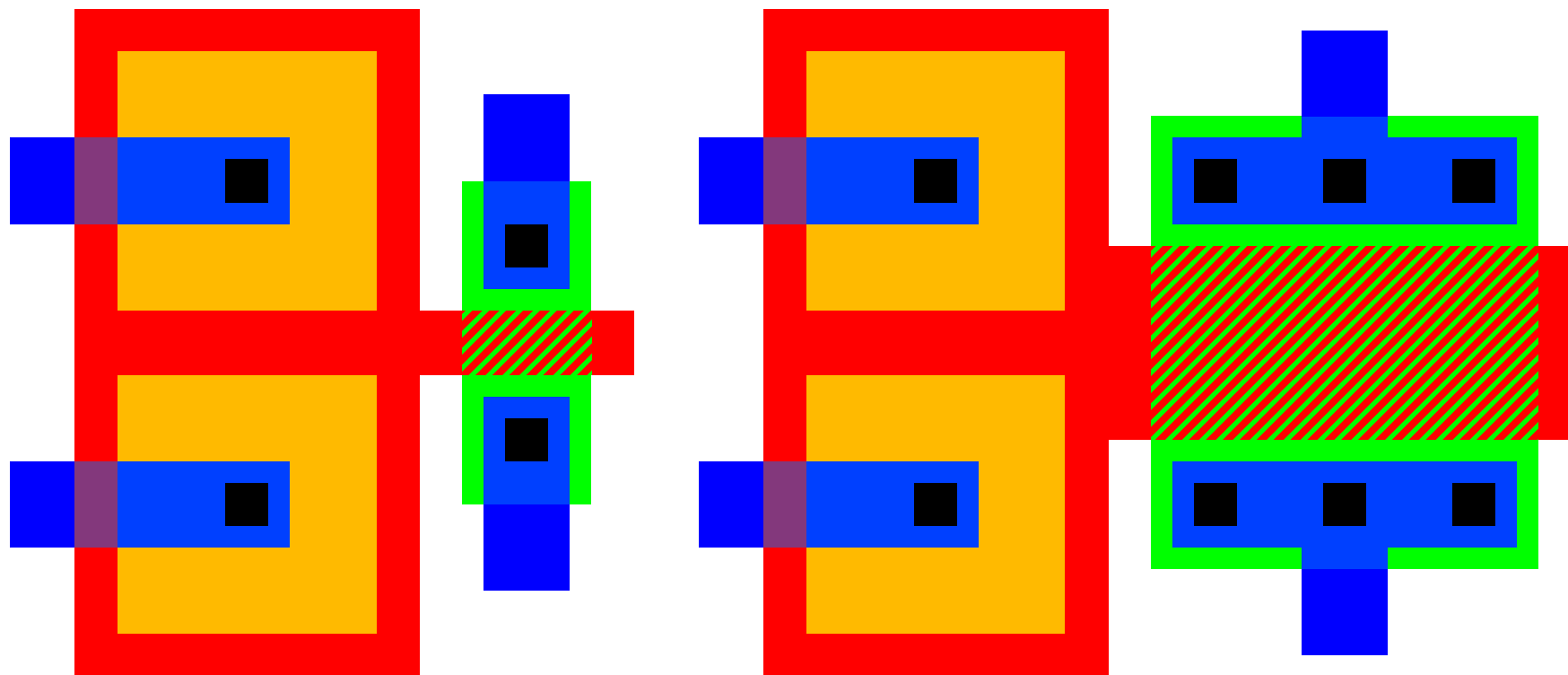


- ▶ Be careful about routing metal lines over top of your floating gates. The voltages on such lines couple into the floating gate just like the control-gate voltages.
- ▶ Moreover, if you are trying to carefully match  $C_T$  for two FGMOS transistors, then you have to count the stray capacitance between these lines and the floating-gate too...

Which FGMOS Transistor Has  
a Higher Output Resistance?

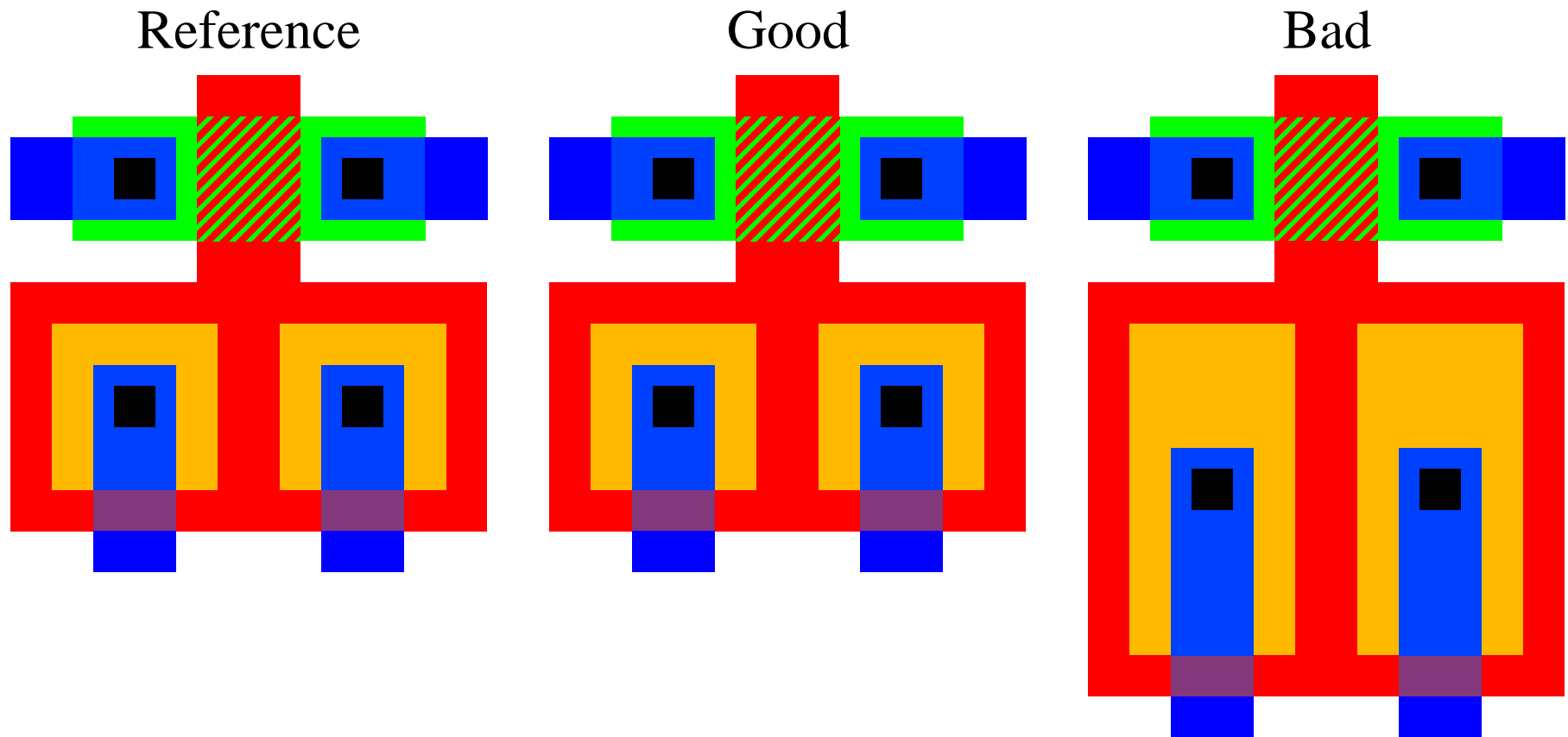


# Which FGMOS Transistor Has a Higher Output Resistance?



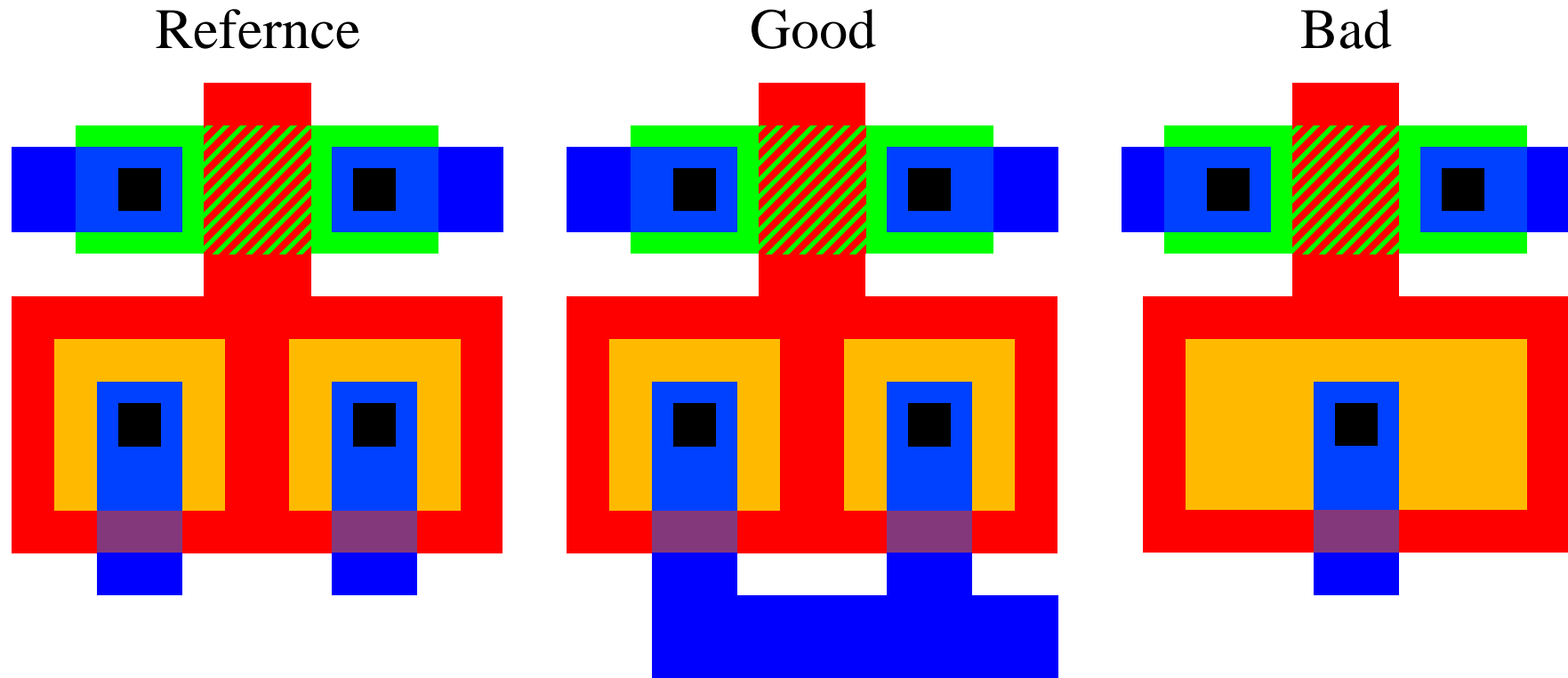
- ▶ The transistor on the *left*...
- ▶ For a FGMOS transistor, the Early effect (i.e., channel-length modulation) is always negligible compared to the effect of  $V_D$  coupling through  $C_{gd}$  to the floating gate. Increasing  $L$  does *not* increase  $r_o$ .
- ▶  $C_{gd} \propto W$ , so making the transistor wider *decreases*  $r_o$ .

# Matching: Same Size & Shape



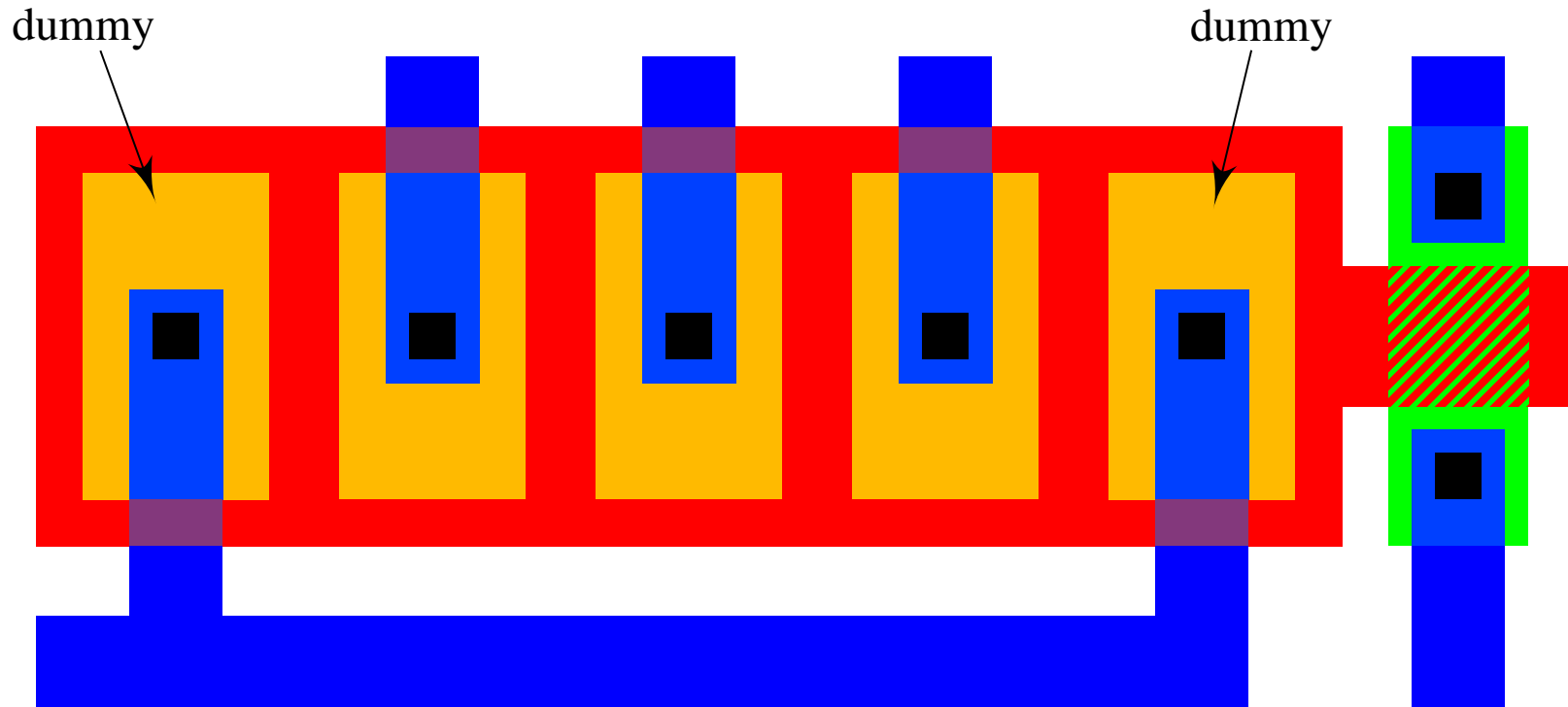
- ▶ To obtain matched capacitive-divider ratios in different FGMOS transistors, use floating gates with identical geometries.
- ▶ Don't forget that  $C_T$  includes parasitics that you won't be able to predict properly at design time.

# Matching: Parallel Unit-Sized Control Gates



- ▶ To obtain accurate control-gate capacitor ratios (e.g., 2:1), connect unit-sized control gates in parallel rather than making composite control gates with the correct area ratios.
- ▶ If you are trying to carefully match  $C_T$ , don't connect the unit-sized control gates on top of the floating gate.

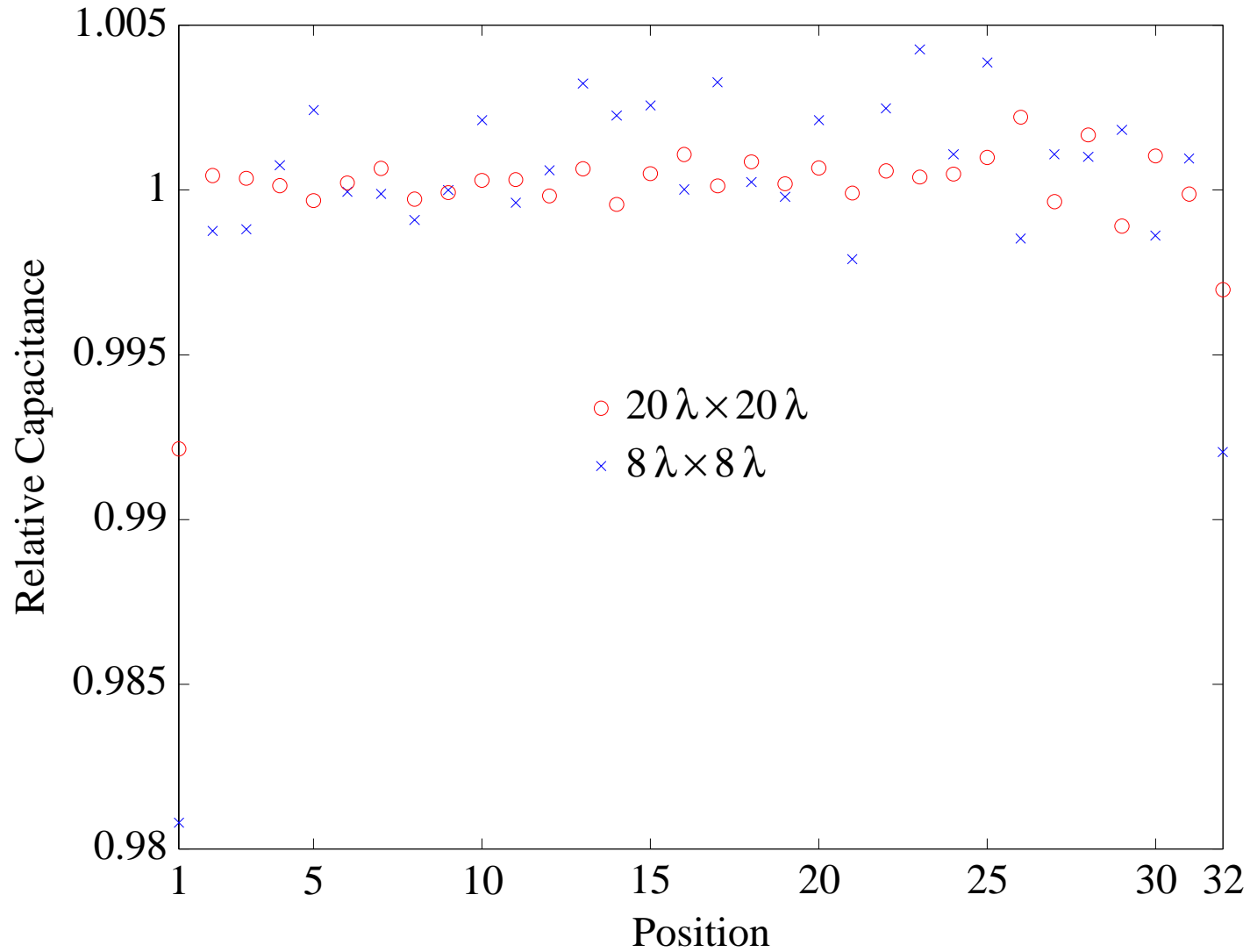
# Matching: Same Surround



- ▶ To improve control-gate matching, use “dummy” control gates at each end to make each “real” control gate have an identical surround.
- ▶ Systematic edge effects are ubiquitous, but the underlying mechanisms are not always clear (e.g., fringing fields, non-uniform etching rates).



# Relative Capacitance vs Position (1.2- $\mu\text{m}$ Process)



# Relative Capacitance vs Position (.35- $\mu\text{m}$ Process)

